



FORM PTO-1449
INFORMATION DISCLOSURE STATEMENT

ATTY DOCKET NO.
51256

SERIAL NO.
10/726,052

APPLICANT(S): Shelnut et al.

FILING DATE:
12/02/2003

ART UNIT:
2874

UNITED STATES PATENT DOCUMENTS

EXAM. INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE
PH	AA	5,064,266	11/12/1991	Sun et al.			
PH	AB	5,439,782	08/08/1995	Haemmerle et al.			
PH	AC	5,761,364	06/02/1998	Knapp et al.			
PH	AD	5,846,694	12/08/1998	Strand et al.			
PH	AE	6,272,275	08/07/2001	Cortright et al.			
PH	AF	2001/0007732	07/12/2001	Iwasaki et al.			

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRAN YES/NO
PH	BA	0 691 554 A1	01/10/1996	Europe			
PH	BB	1 037 073 A2	09/20/2000	Europe			
PH	BC	03-015805	01/24/1991	Japan (Abstract only)			
PH	BD	1993-210020A	08/20/1993	Japan			YES
PH	BE	1994-174952A	06/24/1994	Japan			YES
PH	BF	1994-194533A	07/15/1994	Japan			YES
PH	BG	1999-326665A	11/26/1999	Japan			YES
PH	BH	2000-307090A	11/02/2000	Japan			YES
PH	BI	2001-042150A	02/16/2001	Japan			YES
PH	BJ	2000-056148A	02/25/2000	Japan			YES
PH	BK	2002-116335A	04/19/2002	Japan			YES
PH	BL	2002-202426A	07/19/2002	Japan			YES
PH	BM	2002-258085A	09/11/2002	Japan			YES

OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)

PH	CA	Syms et al., "Reflow and Burial of Channel Waveguides Formed in Sol-Gel Glass on Si-Substrates"; IEEE Photonics Technology Letters, Vol. 5, No. 9, September 1993, pp. 1077-1079.
PH	CB	Sun et al., "Silica-Based Circular Cross-Sectioned Channel Waveguides"; IEEE Photonics Technology Letters, Vol. 3, No. 3, March 1991, pp. 238-240.

Examiner:

Phan V. H. Palma

Date:

06/04/2005



Sheet 1 of 1

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ATTY DOCKET NO.

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UNITED STATES PATENT DOCUMENTS

EXAM. INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FIL. DATE IF APPR
PH	AA	5,064,266	11/12/1991	Sun et al.			
PH	AB	5,230,990	07/27/1993	Yoshimura et al.			
PH	AC	5,846,694	12/08/1998	Deri et al.			
PH	AD	6,319,551	11/20/2001	Bredall et al.			

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRAN YES/NO
PH	BA	1 251 155 A	10/23/2002	Europe			
PH	BB	2 346 452	08/09/2000	Great Britain			

OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)

Examiner:

Phan T.H. Palma

Date:

06/04/05



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FORM PTO-1449 INFORMATION DISCLOSURE STATEMENT	ATTY DOCKET NO. 51256	SERIAL NO. 10/726,052
	APPLICANT(S): Shelnut et al.	
	FILING DATE: 12/02/2003	ART UNIT: 2874

UNITED STATES PATENT DOCUMENTS

EXAM. INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FIL. DATE IF APPR
PH	AA	5,200,487	04/06/1993	Lagarde et al.		—	
PH	AB	5,378,585	01/03/1995	H. Watanabe		—	
PH	AC	5,554,465	09/10/1996	H. Watanabe		—	
PH	AD	5,612,170	03/18/1997	Takemura et al.		—	
PH	AE	5,672,672	09/30/1997	Amano et al.		—	
PH	AF	6,054,253	04/25/2000	Fardad et al.		—	
PH	AC	6,087,064	07/11/2000	Lin et al.		—	
PH	AH	6,088,492	07/11/2000	Kaneko et al.		—	
PH	AI	6,144,795	11/07/2000	Dawes et al.		—	
PH	AJ	6,344,305	02/05/2002	Lin et al.		—	
PH	AK	6,731,857	05/04/2004	Shelnut et al.		—	

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRAN YES/NO
PH	BA	WO 98/26315	06/18/1998	International		—	
PH	BB	0 543 761 A1	05/26/1993	Europe		—	
PH	BC	8-304644	11/22/1996	Japan		—	Yes
PH	BD	8-259895	10/08/1996	Japan		—	Yes
PH	BE	6-172533	06/21/1994	Japan		—	Yes
PH	BF	6-256523	09/13/1994	Japan		—	Yes

Examiner: *Phom T. H. Palmer*

Date: *06/04/2005*

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EXAM. INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FIL. DATE IF APPR
	BG	31 33039	11/24/2000	Japan			Yes
	BH	10-253845	09/25/1998	Japan			Yes
	BI	10-148729	06/02/1998	Japan			Yes
	BJ	8-327842	12/13/1996	Japan			Yes
	BK	06-172533	06/21/1994	Japan			Abstract
	BL	57-168246	10/16/1982	Japan			Abstract
	BM	58-096654	06/08/1983	Japan			Abstract
	BN	63-279245	11/16/1988	Japan			Abstract
	BO	04-271306	09/28/1992	Japan			Abstract
	BP	04-366958	12/18/1992	Japan			Abstract
	BQ	2003-3048984A	02/21/2003	Japan			Abstract
OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)							
	CA	Bagley et al., "The Processing and Use of Organosilicon Polymers for Photonic Applications"; Polymer Engineering and Science, Mid-September 1989, Vol. 29, No. 17, pp. 1197-1199.					
	CB	Brault et al., "Bilevel Polysiloxane Resist for Ion-Beam and Electron-Beam Lithography"; SPIE Vol. 539 Advances in Resist Technology and Processing II (1985); pp. 70-73.					
Examiner:				Date:			